

Title (en)  
Aqueous acid galvanic bath.

Title (de)  
Wässriges saures galvanisches Bad.

Title (fr)  
Bain acide aqueux galvanique.

Publication  
**EP 0244685 A1 19871111 (DE)**

Application  
**EP 87105754 A 19870418**

Priority  
DE 3613874 A 19860424

Abstract (en)  
1. An aqueous acid electroplating bath for the electrolytic deposition of zinc containing as essential assistants a conducting salt, a brightener and a surfactant, wherein the surfactant is a compound of the formula see diagramm : EP0244685,P8,F1 where R is CH<sub>3</sub> - or CH<sub>3</sub>-CH<sub>2</sub> -, x and z are each from 0 to 49, y is from 1 to 25, x+y+z is from 3 to 50, R<sup>\*\*1</sup> is C<sub>4</sub> - to C<sub>20</sub> -alkyl, R<sup>\*\*2</sup> is H or C<sub>4</sub> - to C<sub>20</sub> -alkyl and Me is H, an alkali metal atom or one equivalent of an alkaline earth metal or zinc atom.

Abstract (de)  
Wäßriges saures galvanisches Bad zur elektrolytischen Abscheidung von Zink, wobei das Bad als wesentliche Hilfsmittel Leitsalze, Glanzbildner und als Tenside Verbindungen der Formel <IMAGE> enthält, in der R = CH<sub>3</sub>-, CH<sub>3</sub>-CH<sub>2</sub>- x, z = 0 bis 49, y = 1 bis 25, x+y+z = 3 bis 50 R<sup>1</sup> = C<sub>4</sub>- bis C<sub>20</sub>-Alkyl, R<sup>2</sup> = H, C<sub>4</sub>- bis C<sub>20</sub>-Alkyl und Me = H, Alkalimetallatom oder ein Äquivalent eines Erdalkalimetall- oder Zinkatoms bedeuten.

IPC 1-7  
**C25D 3/22**

IPC 8 full level  
**C25D 3/22** (2006.01)

CPC (source: EP)  
**C25D 3/22** (2013.01)

Citation (search report)  
• [AD] EP 0115020 A2 19840808 - BASF AG [DE]  
• [A] US 4270990 A 19810602 - FONG JAAN J

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DE FR GB

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**EP 0244685 A1 19871111; EP 0244685 B1 19890726; DE 3613874 A1 19871029; DE 3760367 D1 19890831**

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